

POROUS SILICON UNIT μ PORSI



The porous silicon formation system μ PorSi is a sufficient wet chemical solution for porous silicon formation and electropolishing of silicon. Together with our Power Supply PS2, MOT offers an all-in-one solution for this range of fabrication methods. As an option, an optical windows allows for light-assisted porous silicon formation. Because of the flexible arrangement and build-up, the porous silicon formation system μ PorSi is the ideal tool either for industrial or R&D demands. Of course, customized solutions are available after clearing the technical details.

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Data sheet

Wafer Sizes: up to 300mm

Applications: MEMS, CMOS, Sensor, PV, R&D or
Production Type

ETCHING MODULES

- Overflow circulation with filtration
- Customized Chamber amount selection
- PLC controlled
- Touch Panel for easy operation

RINSING MODULE

- Standard: Overflow Rinse
- Optional: QDR, Pentane, IPA

BUILD-UP

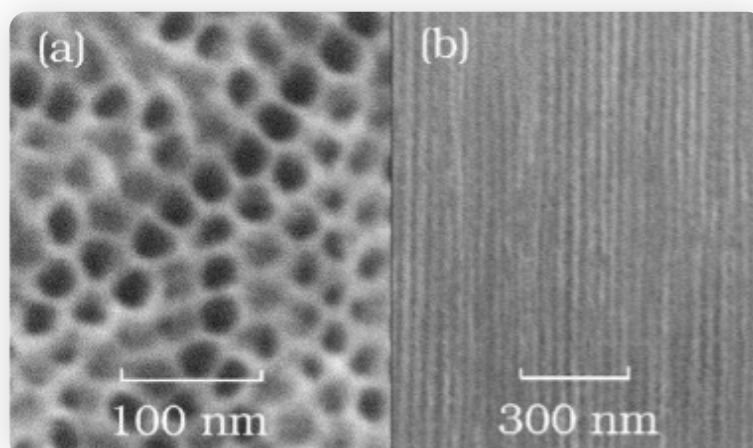
- Material: PP white
- Door material: PVC transparent
- PP plumbing, optional PVDF or PFA tube with PFA Flaretek Fittings
- Access Panel: Touch Panel

OPERATING ELEMENTS

- All process operating elements are integrated into the front panel
- All electrical and pneumatically components are integrated in an independent compartment in the back side service area,
- DIW- and N₂-Spray gun integrated in the working surface

General OPTIONS

- Automatic Handling (Ready for Robot Handling)
- Light assisted porous silicon formation
- fully metal-ion free wafer processing possible
- Internal Chemical Management
- Integration of pre/post process cells, Laminar-Flow-Units
- Execution as fume hood
- FM 4910 proofed material



For further questions or demands, please feel free to contact us under www.mot-semicon.com or contact@m-o-t.info

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